Society Announces Hackerman Young Author Award Winners

The Society is please to announce the recipients of the Norman Hackerman Young Author Awards for 1996, Jan Halvor Nordlien (ES&T) and Jewon Lee (SSS&T), for their excellent work which has appeared in the **Journal.**

Jan Halvor Nordlien received his M.S. degree in Materials Physics from the Norwegian University of Science and Technology (NTNU) in Trondheim, Norway in 1991. From 1991 to 1995 he worked at the Department of Electrochemistry at NTNU with Professor Kemal Nisancioglu, performing doctoral work on characterization of naturally formed oxide film on magnesium and magnesium alloys using surface analytical techniques such as X-ray photoelectron spectroscopy (XPS) and transmission electron microscopy (TEM).

Nordlein received his Ph.D. in 1995. After doing his military duty in 1996, Mr. Nordlien joined SINTEF, the Foundation for Technical and Industrial Research at the University in Trondheim, in 1997. Mr. Nordlien is currently working as a postdoctoral student studying filiform corrosion on aluminum rolled products. The aim is to understand the filiform corrosion mechanism and the importance of the thermo-mechanical history of the metal when it comes to filiform corrosion susceptibility, using electrochemical and surface analytical techniques.

Jewon Lee received his B.S. degree in Inorganic Materials Engineering from the Hanyang University in Korea (1993), his M.S. degree at the University of Florida (1995) and will receive his Ph.D. degree from the Department of Materials Science and Engineering in 1997, under the guidance of Prof. Stephen J. Pearton.

Lee was a contract engineer at Sandia National Laboratories. He was a visiting scientist at Bell Laboratories, Lucent Technologies, Murray Hill, NJ; he consulted for Samsung Electronics in Korea in 1997.

His research has covered a variety of areas in semiconductor device processing, including wet and dry etching, plasma enhanced chemical vapor deposition, ion implantation, surface degradation, device damage, hydrogen passivation, rapid thermal annealing and plasma process modeling. He has developed plasma etching recipes for compound semiconductors, oxides, metals and flat panel displays with both electron cyclotron resonance and inductively coupled plasma sources, which has led to several graduate student awards.

He is an author of over 80 journal papers and 50 conference papers. He will start his industrial career in Plasma-Therm Inc., St. Petersburg, Florida in 1998.